

A structural study of the properties of amorphous silica coatings for low internal friction optics

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on behalf of Perugia-Camerino Virgo group



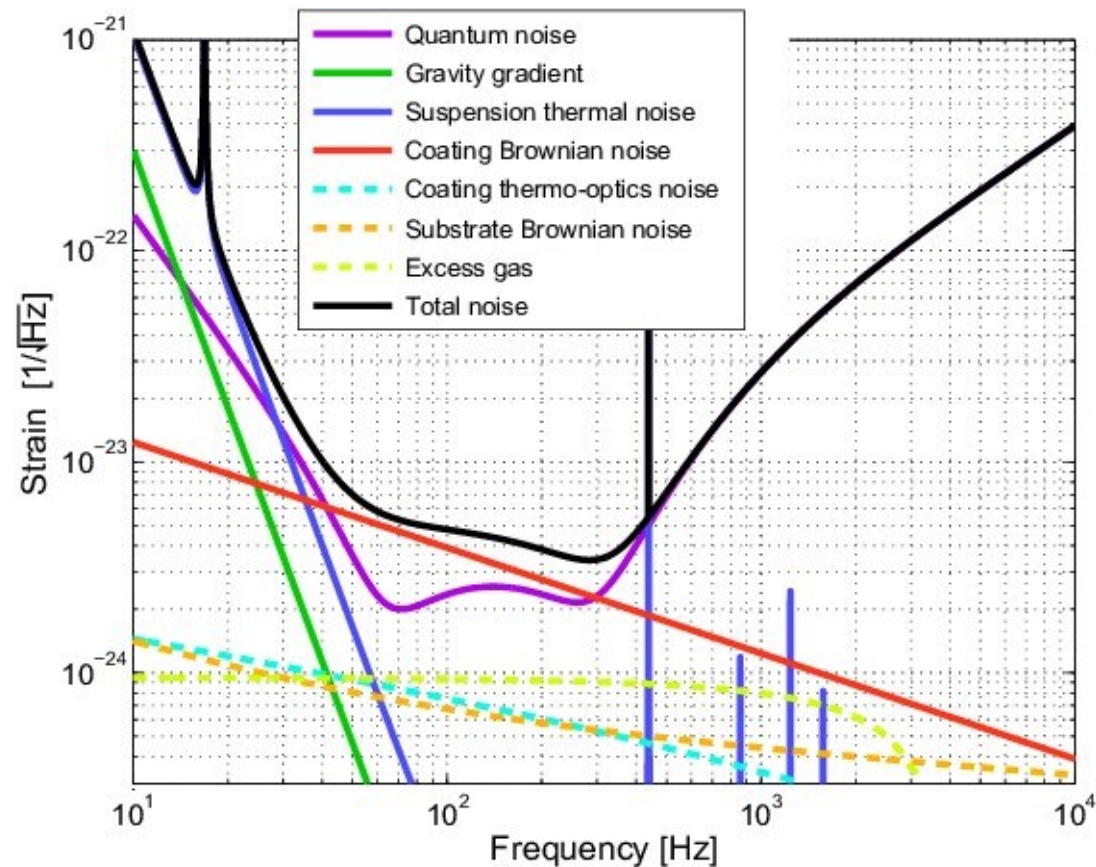
Istituto Nazionale di Fisica Nucleare



Overview

- Coating thermal noise for interferometric mirrors
- Investigation of the structure with different techniques
 - Experiments and results
- Conclusions

Coating thermal noise



EPL Web of Conferences **182**, 02003 (2018)

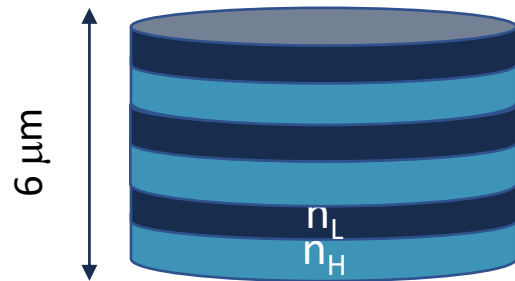
Coating thermal noise (CTN) dominates mid-band frequency sensitivity (40-350 Hz)

$$\text{CTN}(f) \propto \sqrt{\frac{T}{f} \frac{1}{w^2} \varphi d}$$

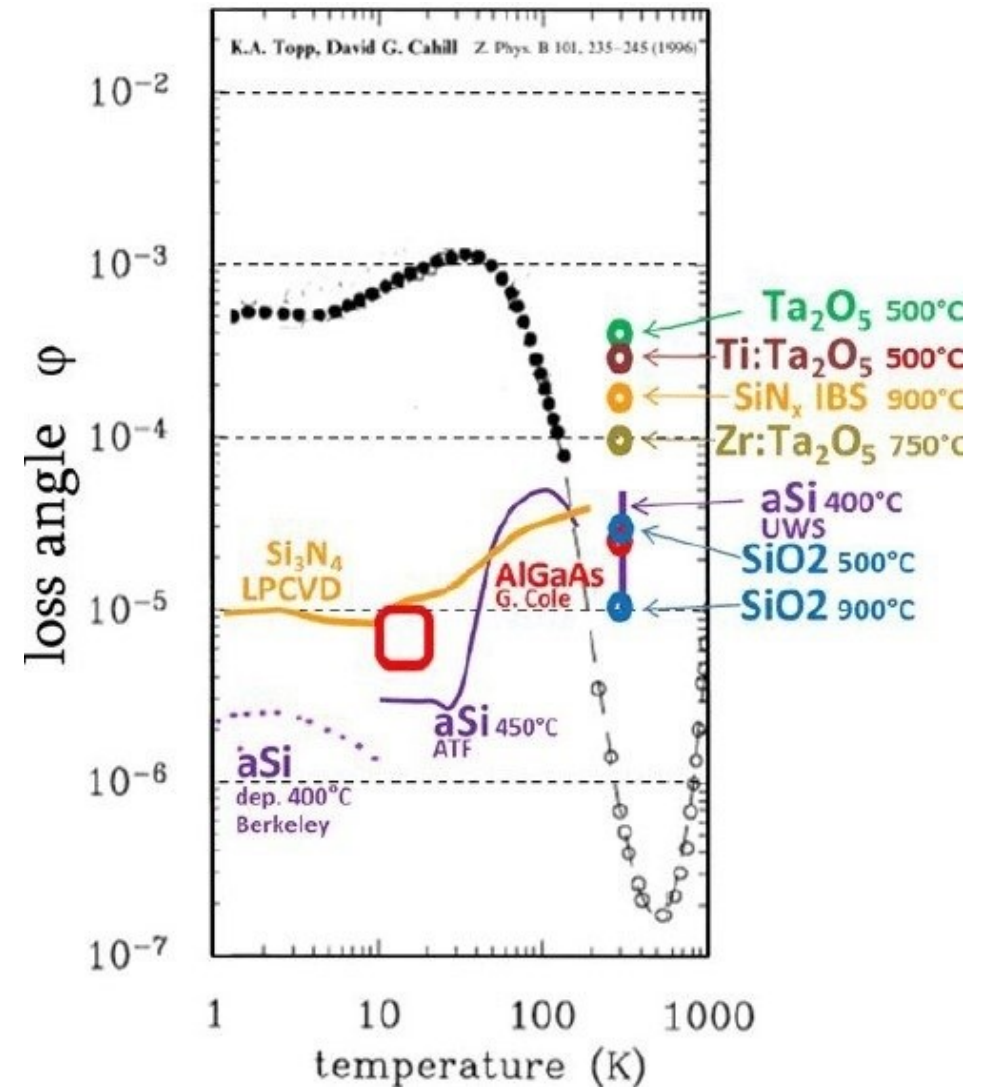
Temperature → T
 Mechanical loss → φ
 Arm length → L
 Beam-size → w
 Coating thickness → d

CTN related to “intrinsic” mechanical loss (fluctuation-dissipation theorem)

Mirror coatings

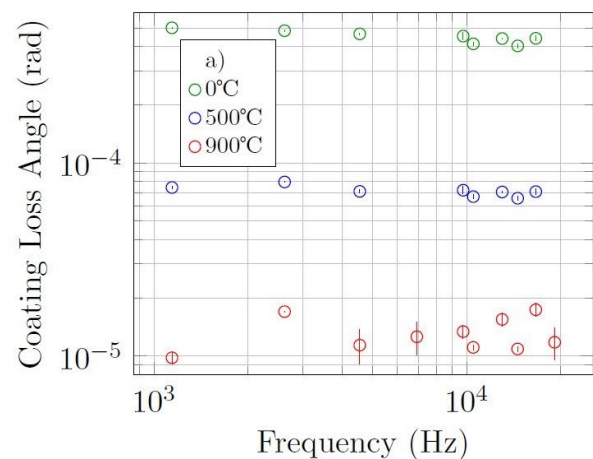
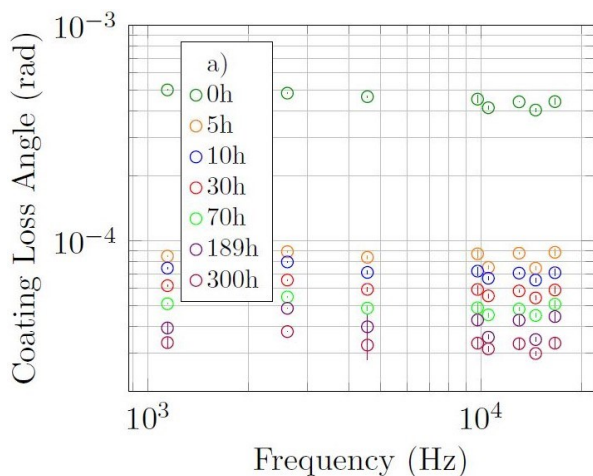


- Alternating materials with high/low refractive index
- Current adVirgo coatings: amorphous Ti(20%):Ta₂O₅ ($n_H=2.07$) and amorphous SiO₂ ($n_L= 1.45$)
- Deposition and post-deposition treatments

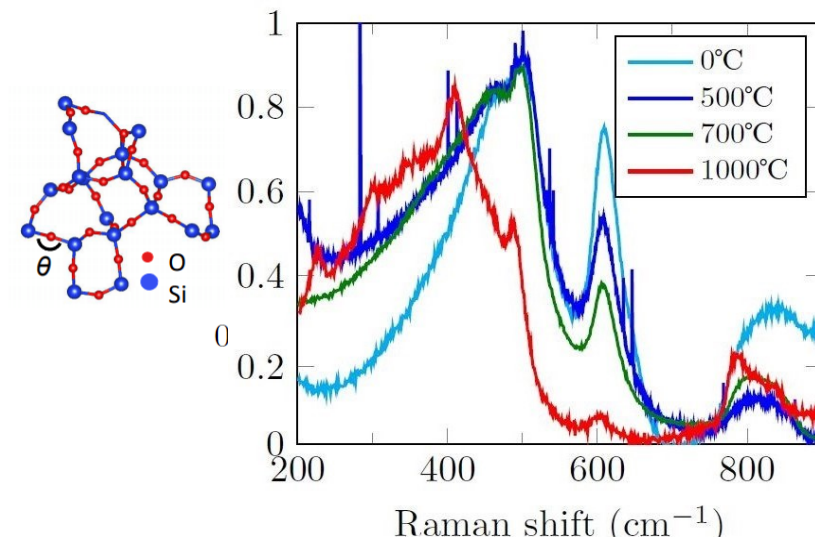
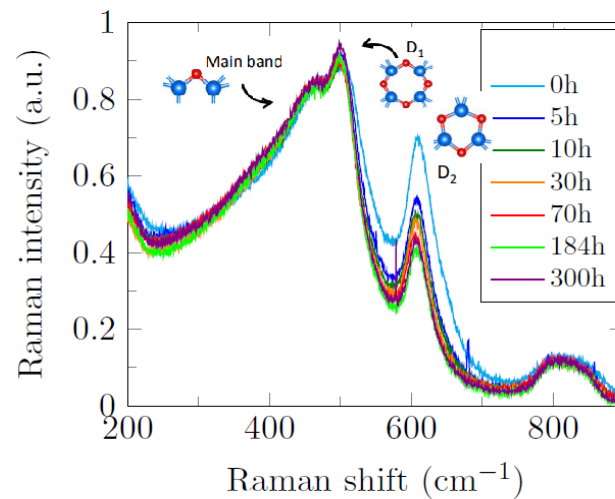


G.Cagnoli on behalf of VCR&D collaboration

SiO₂: status



A. Amato et al., 2018 *J. Phys.: Conf. Ser.* **957** 012006



M. Granata et al., *Physical Review Materials* **2**, 053607 (2018)

A. Amato, *Low Thermal Noise Coating for New Generation Gravitational-Wave Detectors*, Univ. de Lyon (2019)

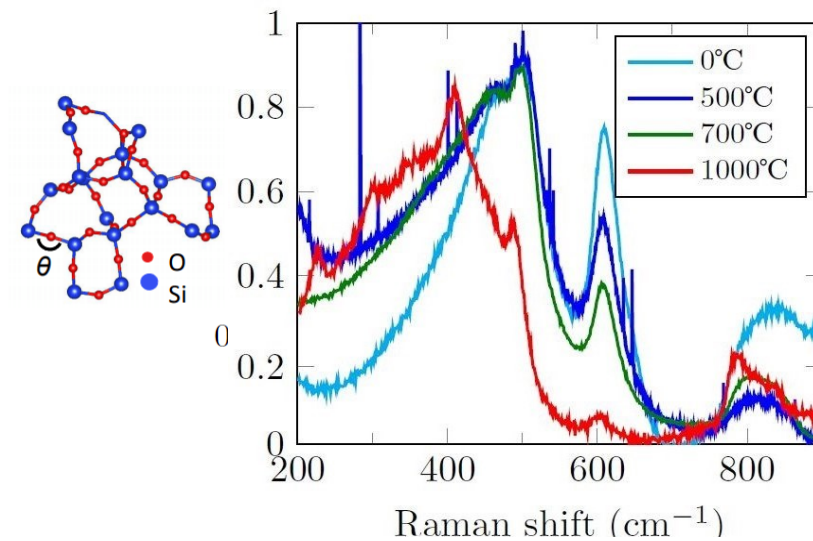
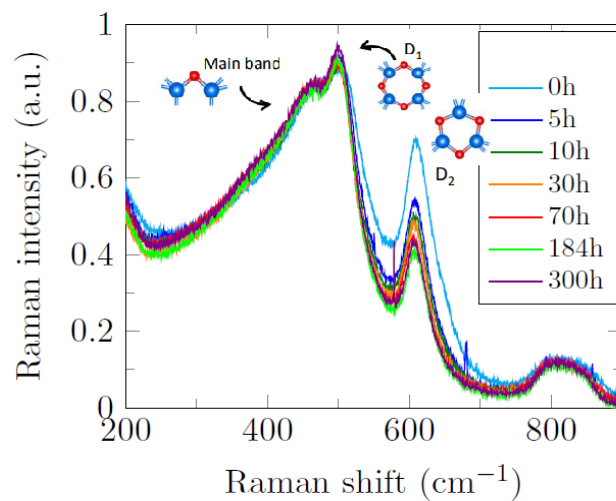
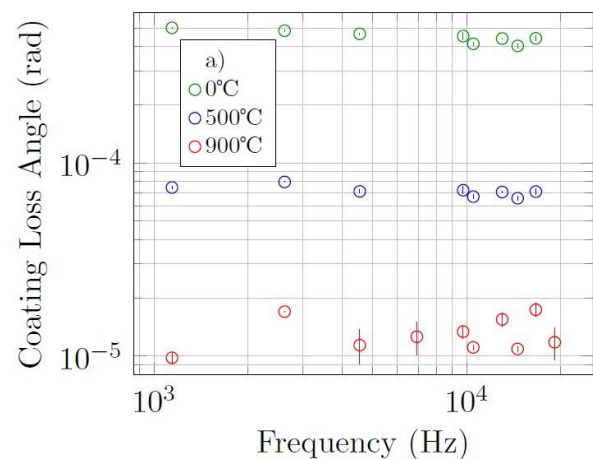
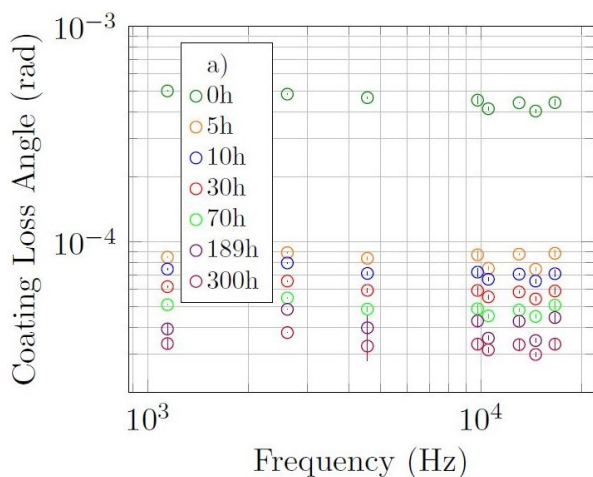
Reduction of mechanical losses at:

- Increasing annealing time (fixed temperature T= 500°C)
- Increasing annealing temperature (fixed time t= 10 hours)

Structure by Raman spectroscopy:

- Shift of the main band to lower frequencies → less dense structure
- Relative area of D₂/D₁ bands → decrease in the 3-fold ring population

SiO₂: status



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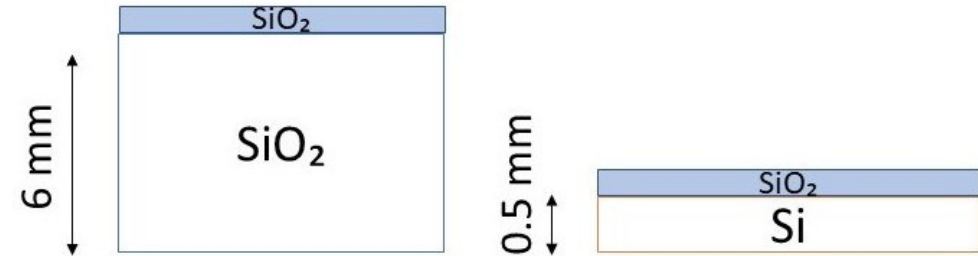
AIM OF THIS STUDY

- Possible correlation between mechanical and structural properties of silica, investigating the structure at different length scales and with techniques complementary to Raman

SiO₂ study

Samples:

- SiO₂ coatings deposited by IBS (LMA, Lyon)
- Si and SiO₂ substrates
- Annealing in air 10 hours up to 1000°C
- Coating nominal thickness: 500-720 nm

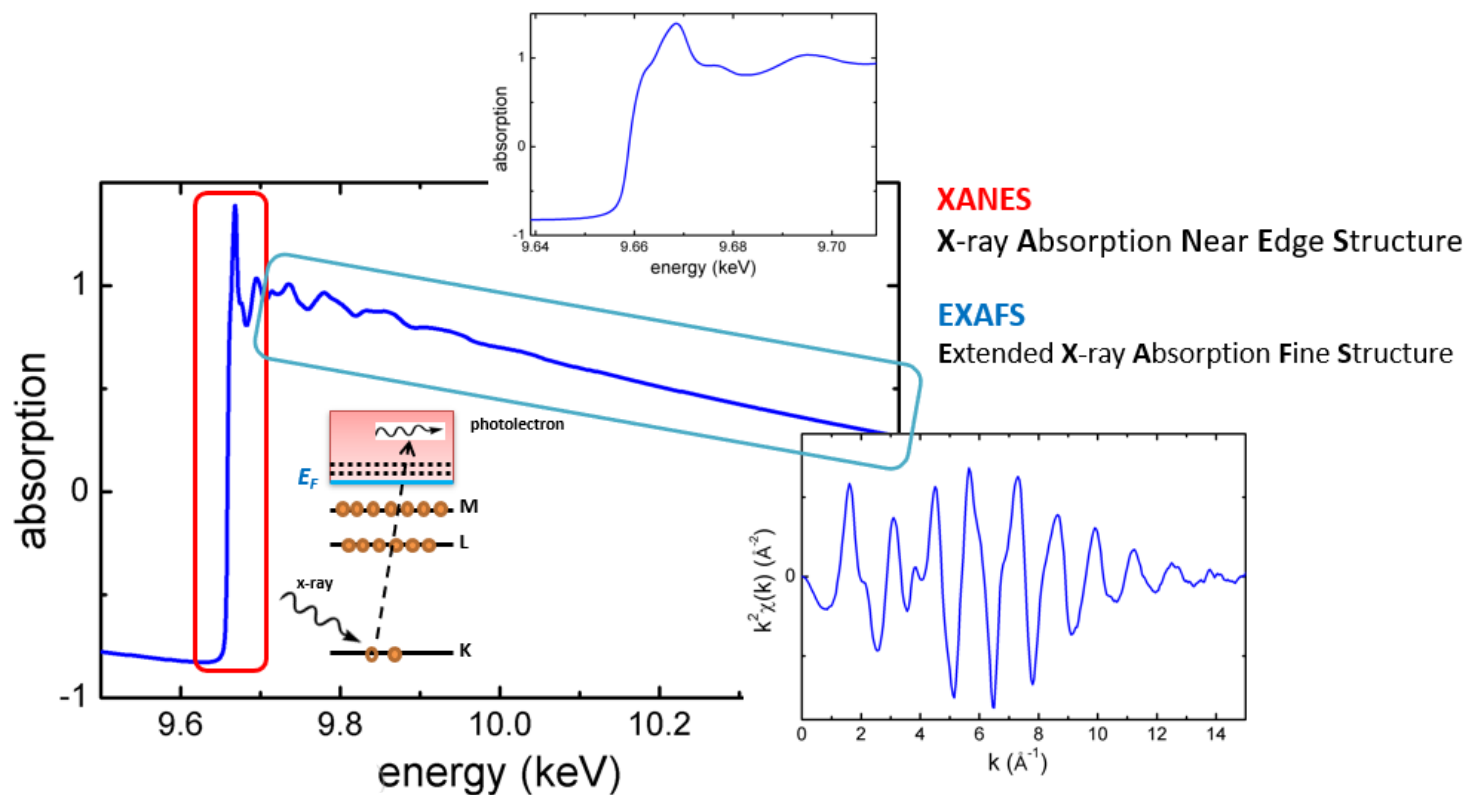


LUCIA beamline
Si K-edge (1839 eV)

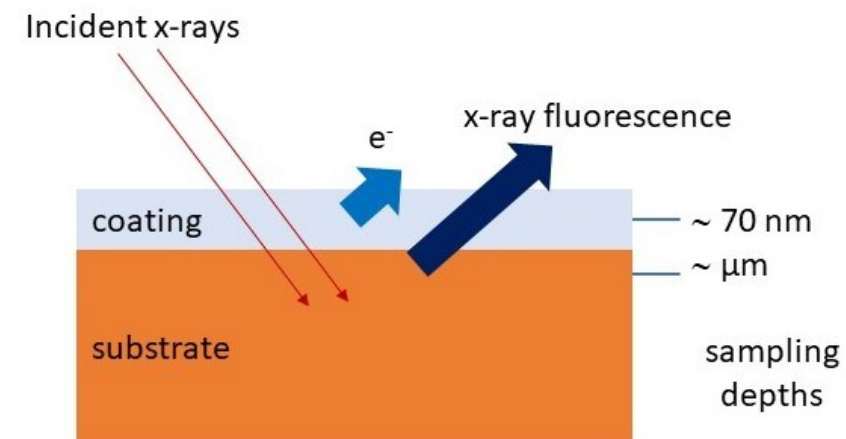
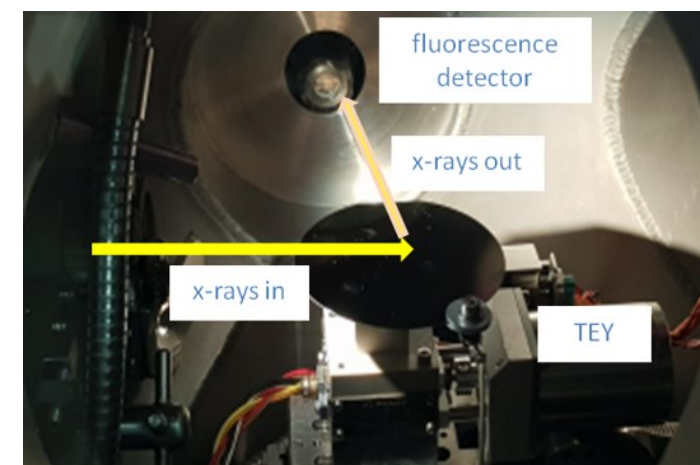
Techniques:

- X-Ray Absorption Spectroscopy
 - XANES (oxidation state and medium range order)
 - EXAFS (local order)
- Grazing Incidence X-Ray Diffraction (structure, crystallization)
- X-Ray Reflectivity (density)
- Fourier Transform Infrared Spectroscopy (short and medium range order)

X-ray Absorption Spectroscopy

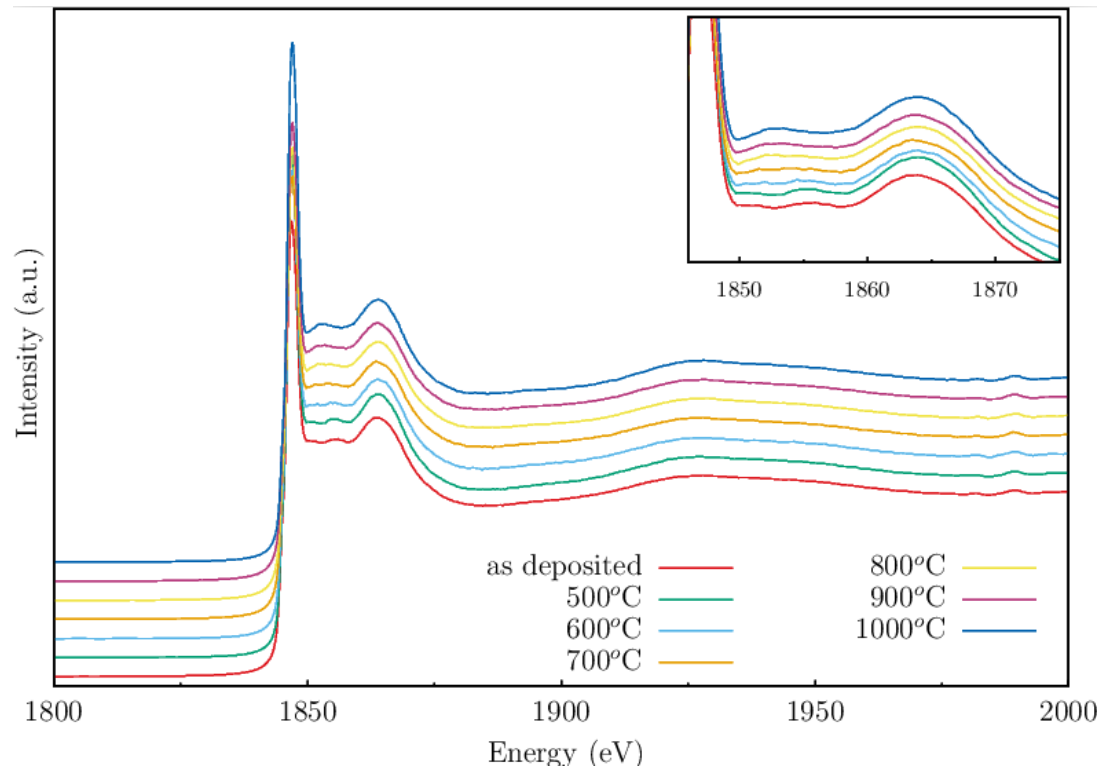


- Synchrotron based technique
- X-ray absorption coefficient μ as a function of the photon energy across the (photoelectric) absorption edge of a specific atom in the material

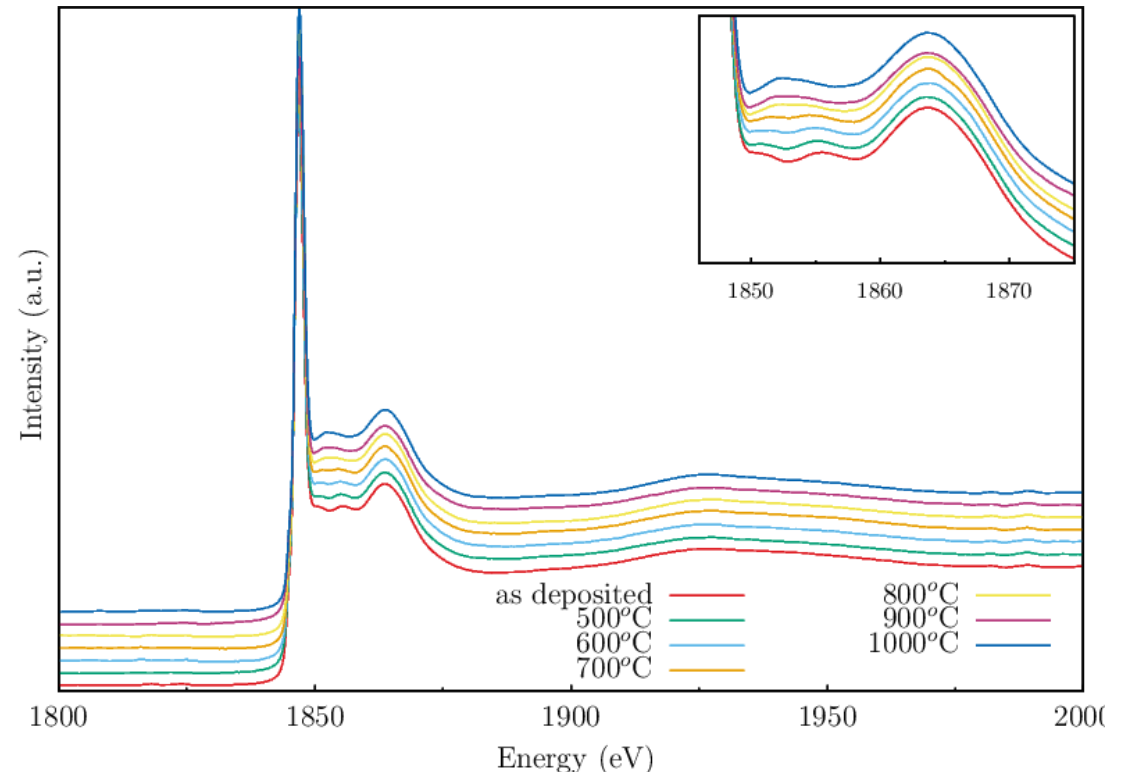


X-ray Absorption Spectroscopy

Fluorescence



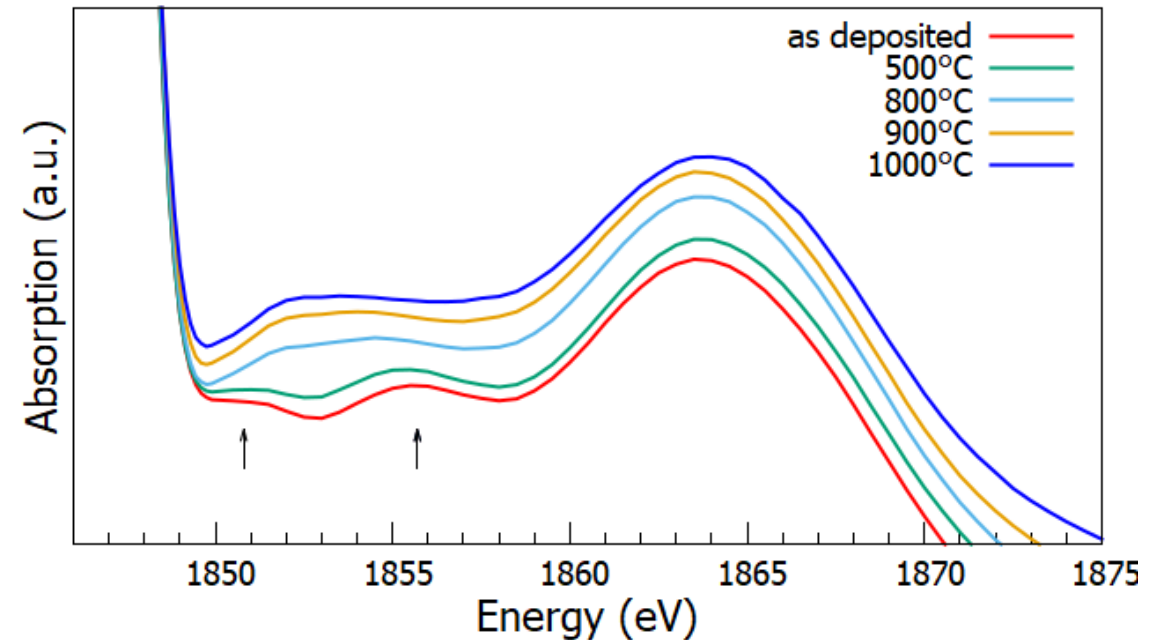
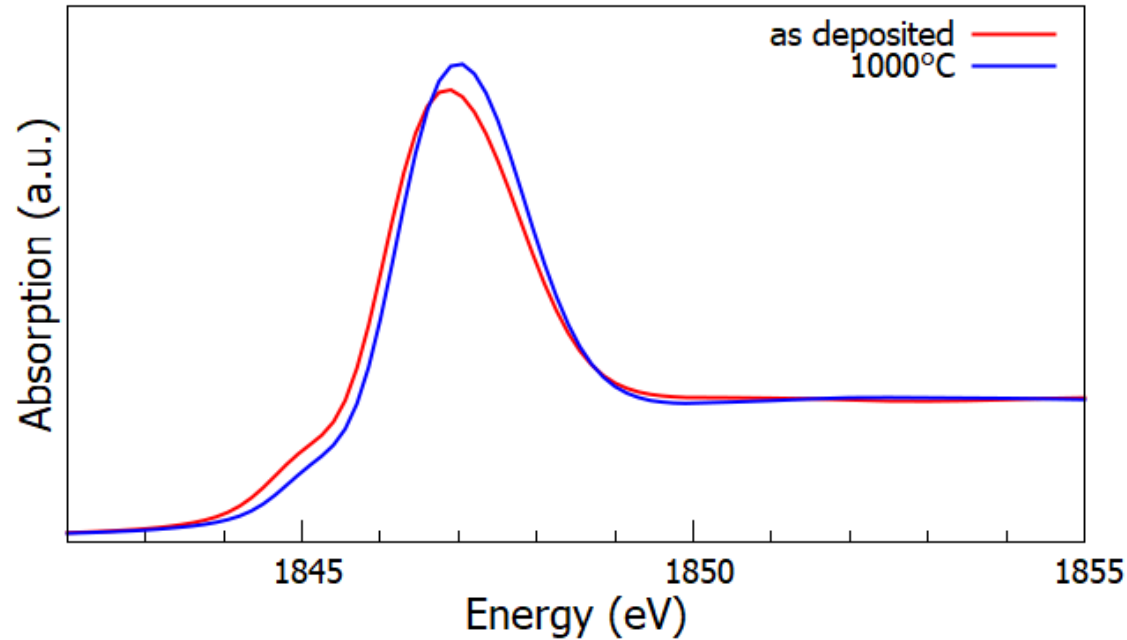
Total electron yield



No differences in the result for different sampling depths

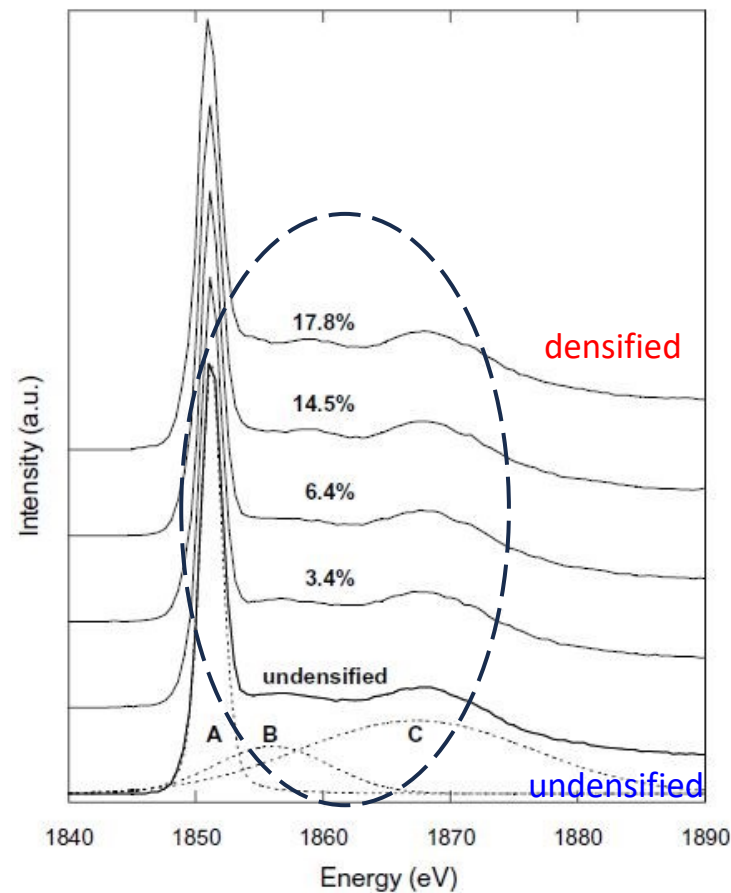
➤ Change occurs within the whole coating depth

XANES

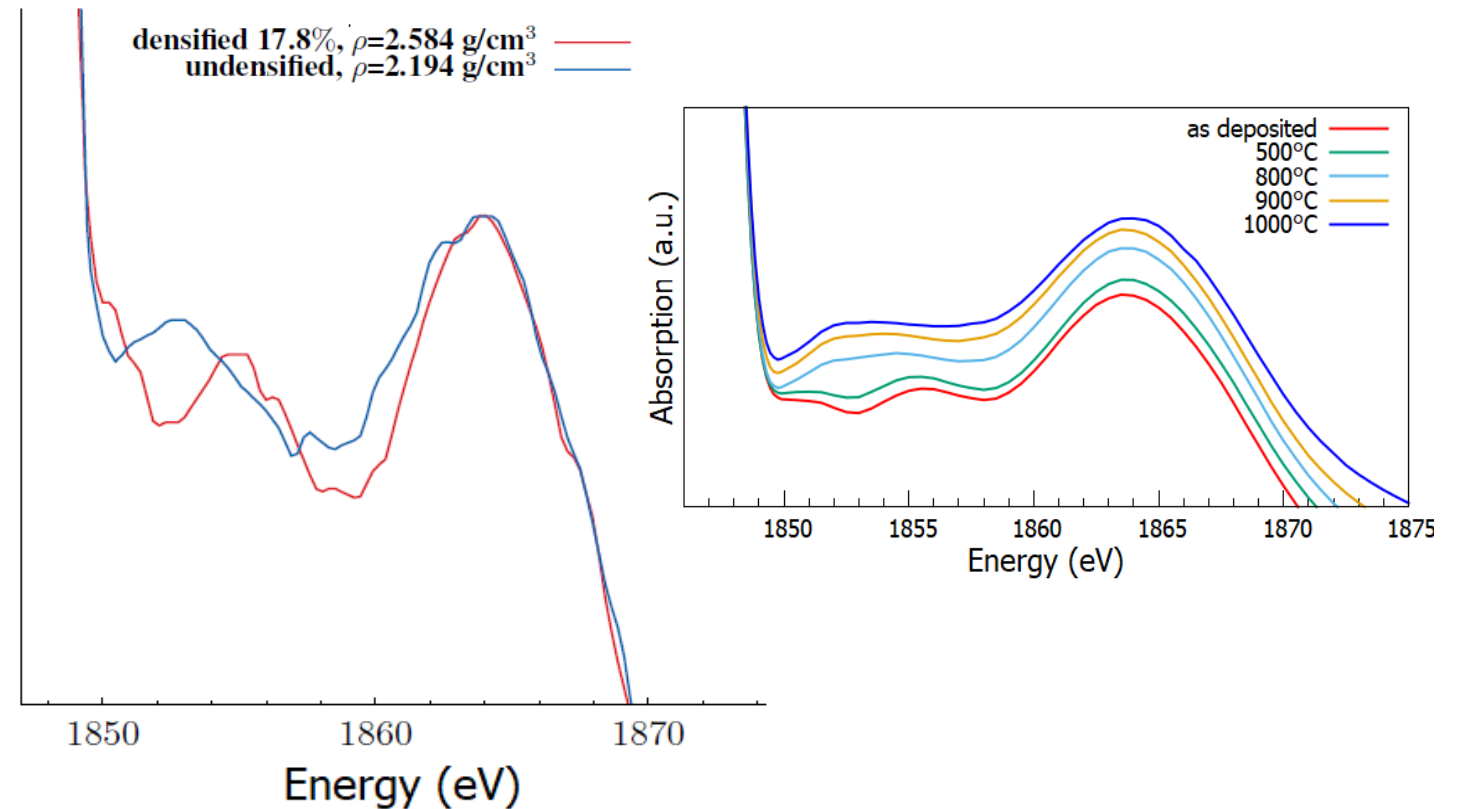


- **Shift of the white line** (~ 0.2 eV) at increasing annealing temperature
- **Change in post-edge region**: the two marked features merge into a single one
- Independent of the sampling depth
- **Independent of the substrate** (Si or SiO₂)

XANES: densified silica glasses



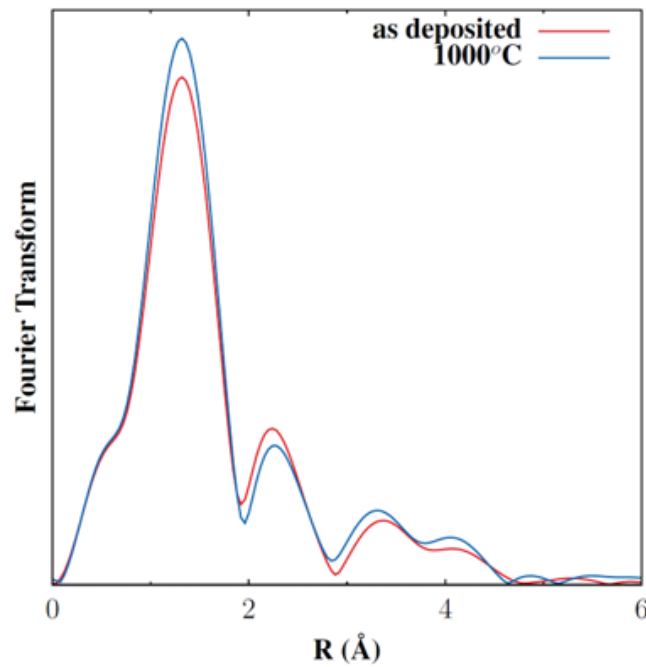
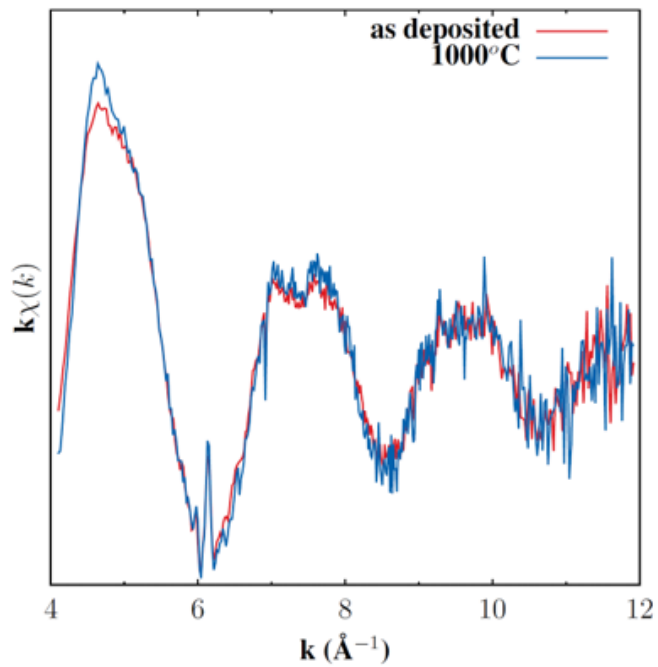
Poe B.T. et al., *Journal of Non-Crystalline Solids* 341 (2004) 162–169



Possible '**undensification**' process associated to **medium range order** effects

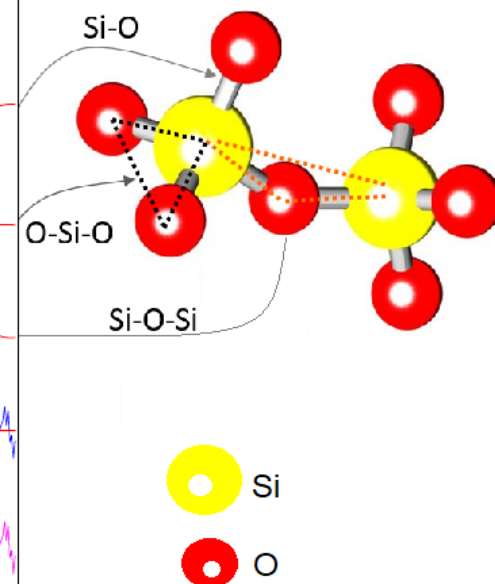
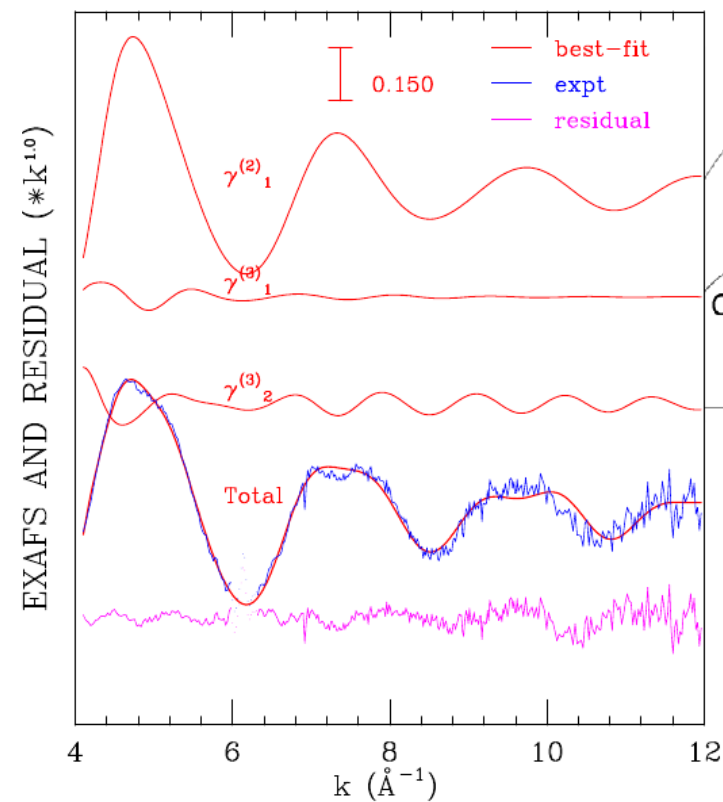
- XANES calculations for different densification levels for a complete interpretation

EXAFS



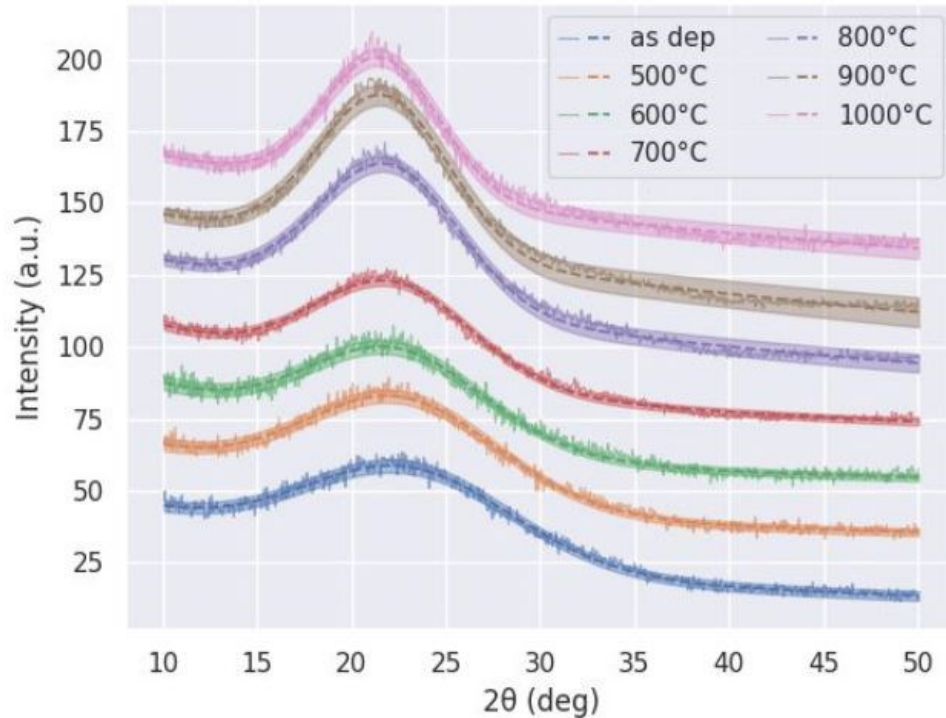
Experimental EXAFS spectra do not change in a significant way with annealing

No changes in the short range structure



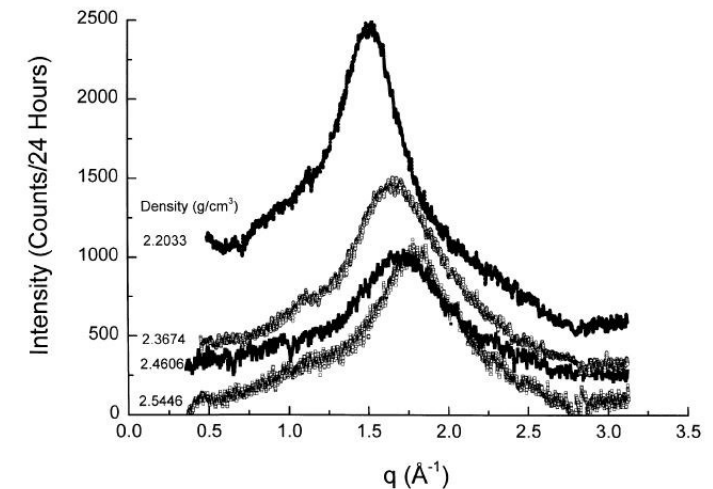


Grazing Incidence X-Ray Diffraction



- The main peak around 22° undergoes a change during annealing
- Same changes (height and peak position) versus density observed for permanently densified silica glasses

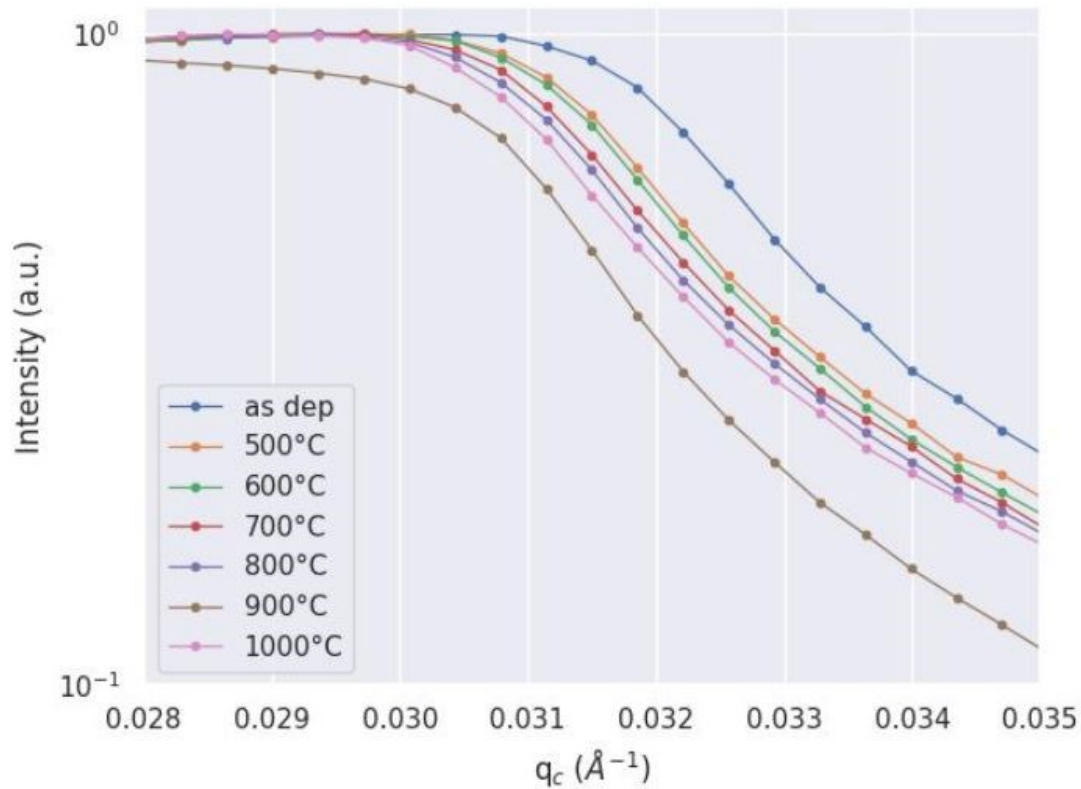
- Collected at University of Padova
- Cu energy ($\lambda = 1.54 \text{ \AA}$)
- Patterns: 2θ range 10°-50°
- No detectable peaks of SiO₂ crystalline polymorphs \rightarrow samples remain amorphous after annealing



C.Z. Tan, J. Arndt, *Jour. Of Non-Cryst. Solids* **249** (1999) 47-50



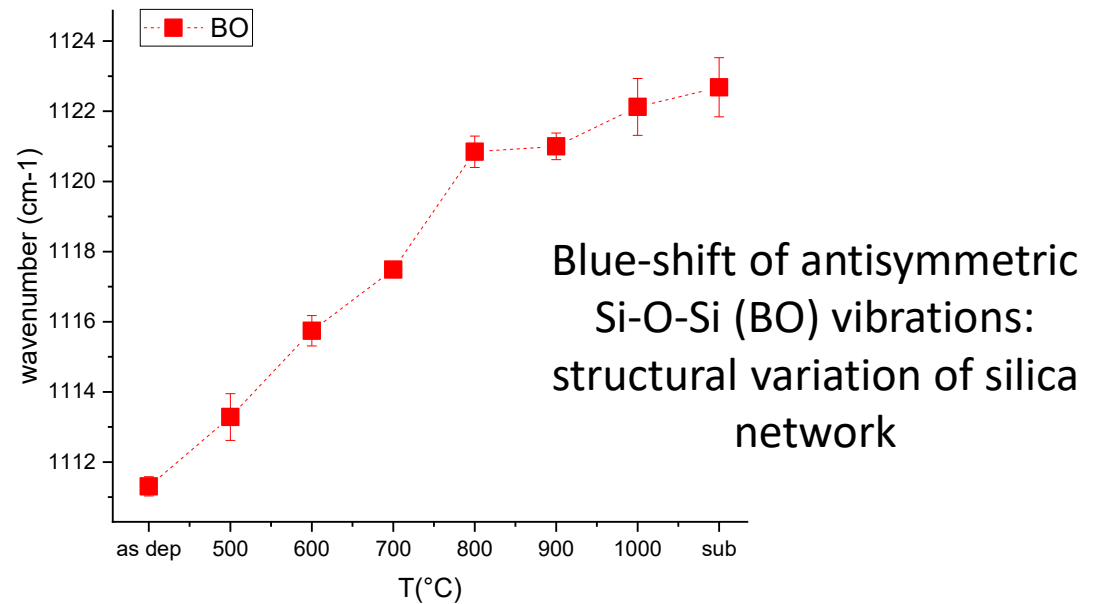
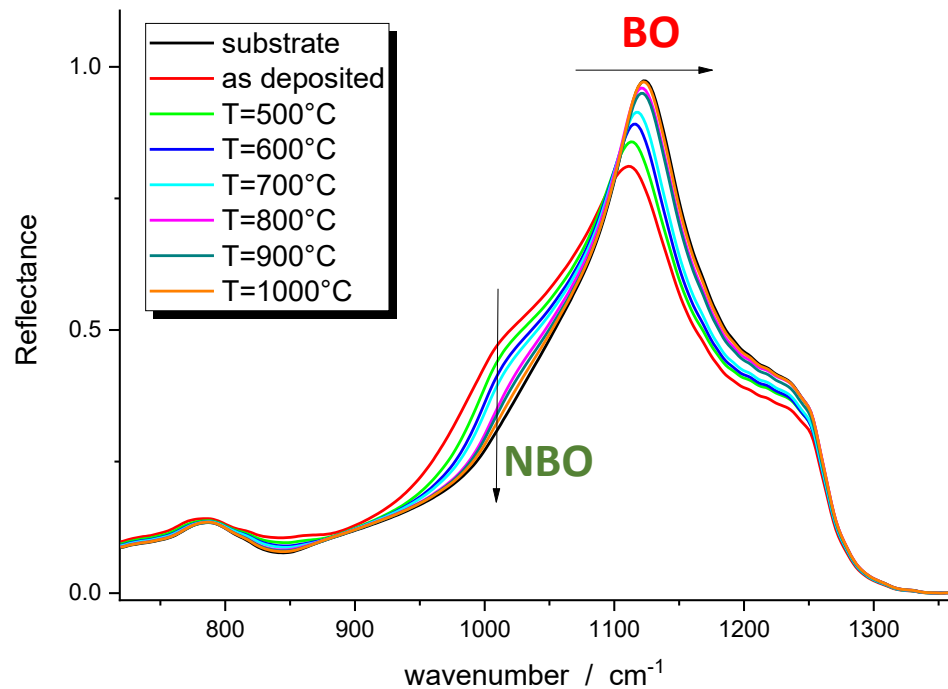
X-Ray Reflectivity



	Density [g/cm ³]	
As Deposited	2.376	Density decreases
500°C	2.291	
600°C	2.278	
700°C	2.251	
800°C	2.234	
900°C	2.212	
1000°C	2.215	

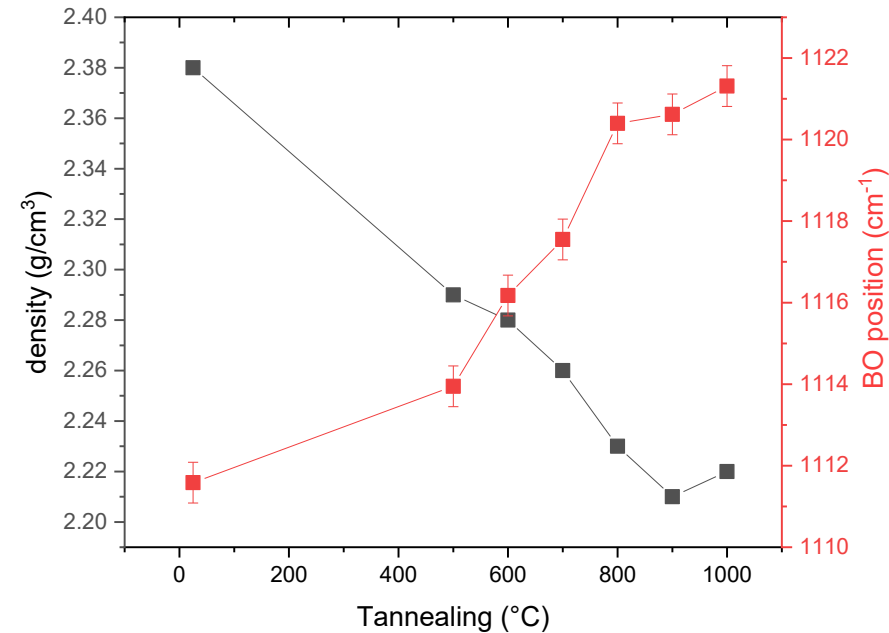
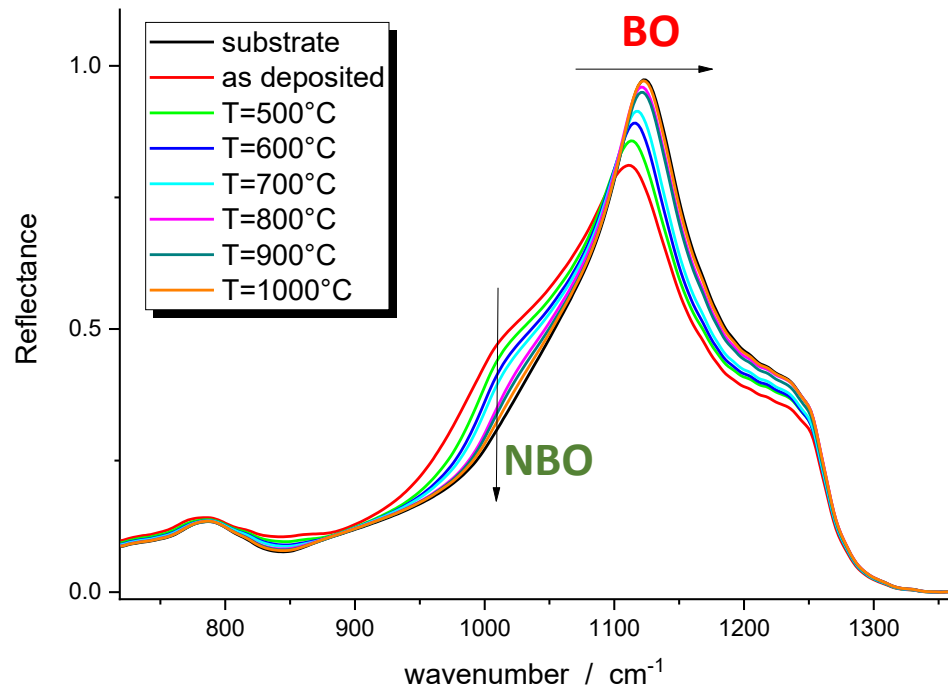
- Films too thick → only density estimation from the critical angle

Fourier Transform Infrared Spectroscopy



- Shift of the fundamental band, correlated to Si-O-Si bond angle, at higher frequencies with increasing annealing temperature → **Medium range order** structural rearrangement, evident at 800°C
- The shoulder at $\sim 1020 \text{ cm}^{-1}$ may suggest the presence of some structural defects (OH groups or **Si-O⁻ non bridging oxygens**) for low annealing temperatures

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Conclusions

- SiO₂ coatings have been investigated for different annealing temperatures and with several complementary techniques
- Spectral changes occur in the XANES region, associated to medium range order effects
- The local structure remains unchanged from EXAFS analysis
- No crystallization peaks of SiO₂ polymorphs with annealing, so the samples remain amorphous. Moreover, a change in the peak of amorphous SiO₂ at 22° is observable
- All the samples exhibit a decrease of the density with respect to the annealing temperature, with XRR
- Medium range order rearrangement is observable from FTIR. The presence of possible defects is under study

Less dense structure at increasing annealing temperature
Local structure unchanged

Collaborators



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